
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Tipton et al.

Attorney Docket No.:
NOVLP075/NVLS-000820

Application No.: NEW

Examiner: UNASSIGNED

Filed: HERewith

Group: UNASSIGNED

Title: METHOD OF POROGEN REMOVAL
FROM POROUS LOW-K FILMS USING
UV RADIATION

INFORMATION DISCLOSURE STATEMENT
37 CFR §§1.56 AND 1.97(b)

Mail Stop Patent Applications
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

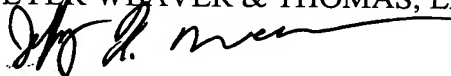
The references listed in the attached PTO Form 1449 may be material to examination of the above-identified patent application. Applicants submit the list of these references in compliance with their duty of disclosure pursuant to 37 CFR §§1.56 and 1.97. The Examiner is requested to make these references of official record in this application. The above-identified application is a Continuation-in-Part of prior application U.S. Patent Application No. 10/404,693. This prior application is being relied upon for an earlier filing date under 35 U.S.C. § 120. Because some of the listed references were either cited by the PTO, or submitted to the PTO in the prior application, under 37 CFR § 1.98(d) Applicants submit that copies of the previously cited references need not be provided.

This Information Disclosure Statement is not to be construed as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that these references indeed constitute prior art.

This Information Disclosure Statement is: (i) filed within three (3) months of the filing date of the above-referenced application, (ii) believed to be filed before the mailing date of a first Office Action on the merits, or (iii) believed to be filed before the mailing of a first Office Action after the filing of a Request for Continued Examination under §1.114. Accordingly, it is believed that no fees are due in connection with the filing of this Information Disclosure Statement. However, if it is determined that any fees are due, the Commissioner is hereby authorized to charge such fees to Deposit Account 500388 (Order No. NOVLP075).

Respectfully submitted,

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Form 1449 (Modified) Information Disclosure Statement By Applicant (Use Several Sheets if Necessary)	Atty Docket No.	Application No.:
	NOVLP075/NVLS-000820	Unassigned
	Applicant:	
	Tipton et al.	
	Filing Date	Group
	HEREWITH	Unassigned

U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
	A1	6,329,017	12/11/01	Liu et al.			
	A2	6,383,466	5/7/02	Domansky et al.			
	A3	6,365,266	4/2/02	MacDougall et al.			
	A4	5,504,042	4/2/96	Cho et al.			
	A5	5,858,457	1/12/96	Brinker et al.			
	A6	6,270,846	8/7/01	Brinker et al.			
	A7	6,387,453	5/14/02	Brinker et al.			
	A8	6,420,441	10/10/99	Allen et al.			
	A9	6,271,273	10/10/00	You et al.			

Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No
	B1							

Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
	C1	Liu et al., "Mesoporous Silica Film From a Solution Containing a Surfactant and Methods of Making Same," U.S. Patent Application Publication No. US2002/0034626, Published March 21, 2002, 27 Pages
	C2	Wu et al., "Use of Multifunctional SI-Based Oligomer/Polymer for the Surface Modification of Nanoporous Silica Films," U.S. Patent Application Publication No. US2002/0001973, Published January 3, 2002, 13 Pages
	C3	Cho et al., "Plasma Treatments of Molecularly Templated Nanoporous Silica Films," Electrochemical and Solid-State Letters, 4 (4) G35-G38 (2001)
	C4	Yung et al., "Spin-on Mesoporous Silica Films with Ultralow Dielectric Constants, Ordered Pore Structures, and Hydrophobic Surfaces," Adv. Mater. 2001, 13, No. 14, 1099-1102
	C5	Schulberg et al., "System for Deposition of Mesoporous Materials," U.S. Patent Application No. 10/295,965, filed November 15, 2002, 64 Pages
	C6	Watkins et al., "Mesoporous Materials and Methods," U.S. Patent Application No.10/301,013, filed November 21, 2002, 34 Pages

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	Filing Date	Group
	HEREWITH	Unassigned

	C7	Justin F. Gaynor, "In-Situ Treatment of Low-K Films With a Silylating Agent After Exposure To Oxidizing Environments," U.S. Patent Application No.10/056,926 filed January 24, 2002, 34 Pages
	C8	Gangpadhyay et al., "The First International Surface Cleaning Workshop," Northeastern University, November 11-14, 2002
Examiner		Date Considered

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.